



## ABSTRACT

5 SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING METHOD.

A substrate processing apparatus is disclosed, comprising:

a first zone for heating the substrate;

a second zone being disposed adjacent to the first zone along a first direction, for

10 regulating a temperature of the substrate to a predetermined temperature;

a third zone being disposed approximately perpendicular to the first direction adjacent to the second zone, for delivering and receiving the substrate to/from the second zone;

wherein the second zone has a delivering position for delivering and receiving the

substrate to/from the third zone, and a mechanism transferring the substrate between the

15 delivering position and the first zone.

Fig. 1